Day: Tuesday Date: 4/8/2003



## PALM INTRANET

Time: 11:37:09

### **Inventor Name Search Result**

Your Search was:

Last Name = INAGAKI First Name = NORIHIRO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10058925	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	INAGAKI, NORIHIRO
09793879	Not Issued	030	02/28/2001	METHOD AND SYSTEM FOR PYROLYZING PLASTIC AND PYROLYSATE PRODUCT	INAGAKI, NORIHIRO
09680268	6472080	150	10/06/2000	THIN COPPER FILM DIRECTLY BONDED POLYIMIDE FILM AND METHOD OF MANUFACTURING THE SAME	INAGAKI, NORIHIRO
<u>09586790</u>	Not Issued	161		GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	INAGAKI, NORIHIRO
<u>07563321</u>	5086286	150	07/26/1990		INAGAKI , NORIHIRO

Inventor Search Completed: No Records to Display.

	Last Name	First Name	
Search Another:	INAGAKI	NORIHIRO	•••••••••••••••••••••••••••••••••••••••
Inventor		Search	

Day: Tuesday Date: 4/8/2003



# **PALM INTRANET**

Time: 11:37:20

#### **Inventor Name Search Result**

Your Search was:

Last Name = TASAKA First Name = SHIGERU

Application#	Patent#	Status	Date Filed	Title	Inventor Name
<u>10058925</u>	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	TASAKA, SHIGERU
<u>09793879</u>	Not Issued	030	02/28/2001 ·	METHOD AND SYSTEM FOR PYROLYZING PLASTIC AND PYROLYSATE PRODUCT	TASAKA, SHIGERU
09680268	6472080	150	10/06/2000	THIN COPPER FILM DIRECTLY BONDED POLYIMIDE FILM AND METHOD OF MANUFACTURING THE SAME	TASAKA, SHIGERU
<u>09586790</u>	Not Issued	161	06/05/2000	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	TASAKA, SHIGERU
<u>06657196</u>	4607386	150	10/03/1984	HANDWRITTEN CHARACTER RECOGNITION DEVICE	TASAKA, SHIGERU
06651778	4591465	150	09/18/1984	METHOD OF PRODUCING POLYMERIC ELECTRET ELEMENT	TASAKA, SHIGERU

Inventor Search Completed: No Records to Display.

Day: Tuesday Date: 4/8/2003



# PALM INTRANET

Time: 11:38:02

## **Inventor Name Search Result**

Your Search was:

Last Name = NAKAJIMA First Name = TETSUYA

Ali-otio-#	Patent#	Status	Date Filed	Title	Inventor Name
Application# 10058925	Not Issued	030	01/30/2002	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING SAME	NAKAJIMA, TETSUYA
09709423	Not Issued	120	11/13/2000	DIELECTRIC ELEMENT AND METHOD FOR FABRICATING THE SAME	NAKAJIMA, TETSUYA
09586790	Not Issued	161	06/05/2000	GAS BARRIER FILM HAVING POLYPROPYLENE AS A BASE FILM AND METHOD OF MANUFACTURING THE SAME	NAKAJIMA, TETSUYA
09463793	6353078	150	01/27/2000	POLYURETHANE ADHESIVE, METHOD FOR USE IN BONDING, AND USE OF MIXTURE	NAKAJIMA, TETSUYA
09413895	Not Issued	161	10/07/1999	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAJIMA , TETSUYA
09269881	6120969	150	04/02/1999	POLYPHENOL COMPOUND, QUINONEDIAZIDE ESTER	NAKAJIMA , TETSUYA

		T .			
				AND POSITIVE PHOTORESIST COMPOSITION	
<u>09194394</u>	6087466	150	11/25/1998	POLYURETHANES AND POLYESTER POLYOLS	NAKAJIMA , TETSUYA
08575030	5672895	150	12/19/1995	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAJIMA , TETSUYA
08194988	5500542	150	02/14/1994	SEMICONDUCTOR INTEGRATED CIRCUIT WITH PROTECTION CIRCUIT AGAINST ELECTROSTATIC BREAKDOWN AND LAYOUT DESIGN METHOD THEREFOR	NAKAЛMA , TETSUYA
07472585	4971469	150	01/30/1990	AUTOMATIC PAPER LOADING MECHANISM AND METHOD FOR PRINTER	NAKAJIMA , TETSUYA
07323757	4975544	150	03/15/1989	CONNECTING STRUCTURE FOR CONNECTING CONDUCTORS IN AN ELECTRONIC APPARATUS	NAKAJIMA , TETSUYA
06625674	4747083	150	06/28/1984	SEMICONDUCTOR MEMORY WITH SEGMENTED WORD LINES	NAKAJIMA , TETSUYA

Inventor Search Completed: No Records to Display.

	Last Name	First Name
Search Another: Inventor	NAKAJIMA	TETSUYA  Search

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L Number	Hits	Search Text	DB	Time stamp 2003/04/08 09:48
1	45	gilone near? counis6 same (alkoxy methoxy ethoxy) with	USPAT;	2003/04/06 07.46
•		(hydroxy\$1 OH) and (ethanol methanol alcohol) same heat\$4	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
		1 \ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\ \\	USPAT;	2003/04/08 09:19
2	69	silane near2 coupl\$6 same (alkoxy methoxy ethoxy) with (chlor\$6	US-PGPUB;	2005,000 07.11
		halogen) and (ethanol methanol alcohol) same heat\$4	ЕРО; ЛРО;	
			DERWENT;	
1	]		IBM_TDB	
		and	USPAT;	2003/04/08 09:21
3	0	(trialkoxyalkyl\$1silane dialkoxyalkyl\$1silane) near3 coupl\$6 and	US-PGPUB;	
	1	(ethanol methanol alcohol) same heat\$4	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
,	] , [	(trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane) near3 coupl\$6	USPĀT;	2003/04/08 09:23
4	1	(maikoxyaikyi i siiaile diaikoxydiaikyi i siiaile)	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
•	[		IBM_TDB	
=	465	(trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane	USPAT;	2003/04/08 09:25
5	403	methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
	ļ	isobutyltrimethoxysilane dimethyldimethoxysilane	EPO; JPO;	
		dimethyldiethoxysilane) same (coupling coupler)	DERWENT;	
		united systems of the system o	IBM_TDB	
4	154	(trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane	USPAT;	2003/04/08 09:27
6	151	methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	EPO; JPO;	
		dimethyldiethoxysilane) near5 (coupling coupler)	DERWENT;	
			IBM_TDB	2003/04/08 09:29
7	8	((trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane	USPAT;	2003/04/08 09.29
,		methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	EPO; JPO;	,
		dimethyldiethoxysilane) same (coupling coupler) ) same (silica	DERWENT;	
		(silicon near3 (oxide dioxide))) same (plastic polymer	IBM_TDB	
		polypropylene binder)	USPAT;	2003/04/08 09:49
8	2	((trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane	US-PGPUB;	2003/0 // 00
		methyltrimethoxysilane methyltriethoxysilane	EPO; JPO;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	DERWENT;	
	Ì	dimethyldiethoxysilane) near5 (coupling coupler)) same (ethanol	IBM_TDB	
		methanol alcohol) same heat\$4	USPAT;	2003/04/08 09:5
9	2	((trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	EPO; JPO;	
		dimethyldiethoxysilane) near5 (coupling coupler)) same (ethanol	DERWENT;	
		methanol alcohol) same (heat\$4 celsius)	IBM_TDB	
10	2	((trialkoxyalkyl\$1silane dialkoxydialkyl\$1silane	USPAT;	2003/04/08 09:5
10		methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	ЕРО; ЛРО;	
		dimethyldiethoxysilane) same (coupling coupler)) same (ethanol	DERWENT;	
	ì	methanol alcohol) same (heat\$4 celsius)	IBM_TDB	
11	19	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2003/04/08 09:5
11	17	methyltrimethoxysilane methyltriethoxysilane	US-PGPUB;	
		isobutyltrimethoxysilane dimethyldimethoxysilane	ЕРО; ЈРО;	
		dimethyldiethoxysilane) near5 (coupling coupler)) and (ethanol	DERWENT;	
1		methanol alcohol) with (heat\$4 celsius)	IBM_TDB	2002/04/04 17/
	0	(polymer\$4 polyolefin polypropylene polyethylene plastic) neary	USPAT;	2003/04/04 17:0
		surface near9 ((discharge near2 glow) plasma) near9 oxygen near9	US-PGPUB;	
		functionality	EPO; JPO;	.
			DERWENT	5
1	1	I	IBM_TDB	1

				100115 15 00
	452		·,	2002/08/15 17:28
	432	surface near9 ((discharge near2 glow) plasma) near9 (oxygen air)	US-PGPUB;	
1	İ	Surface near 9 ((discharge near 2 grow) parties)	EPO; JPO;	:
			DERWENT;	
			IBM_TDB	
	ļ	and a selective polyothylane plastic) near9	USPAT;	2002/08/15 17:22
	501	(polymer\$4 polyolefin polypropylene polyethylene plastic) near9	US-PGPUB;	
		surface near9 ((discharge near2 glow) plasma) near9 (oxygen air	EPO; JPO;	
		hydroxy\$2)	DERWENT;	
	İ		IBM_TDB	
				2002/08/15 17:19
	39	((polymer\$4 polyolefin polypropylene polyethylene plastic) near9	USPAT;	2002/06/15 17:15
	-	surface near9 ((discharge near2 glow) plasma) near9 (oxygen air))	US-PGPUB;	
		near9 hydroxy\$2	EPO; JPO;	
		non's nymonyt-	DERWENT;	
			IBM_TDB	
		((polymer\$4 polyolefin polypropylene polyethylene plastic) near9	USPAT;	2002/08/15 17:23
	18	((polymer\$4 polyolelin polypropytene polyodytene present) surface near9 ((discharge near2 glow) plasma) near9 (oxygen air))	US-PGPUB;	
		surface neary ((discharge nearz glow) plasma) heary (oxygen arr)	EPO; JPO;	
	1	near9 subsequent\$4	DERWENT;	
			IBM TDB	
			USPAT;	2002/08/15 17:39
	75	(polyolefin polypropylene polyethylene) with (hydroxy\$2		2002,00,15 17.57
		functionali\$7) with ((discharge near2 glow) plasma)	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
	22	( polyolefin polypropylene polyethylene) near9 (hydroxy\$2	USPAT;	2002/08/15 17:30
•	33	functionali\$7) near9 ((discharge near2 glow) plasma)	US-PGPUB;	
	1	ninctionalis/) iteal ((discharge float 2 510 tt) processor	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	1	c c (modiff) functionaliss)	USPAT;	2002/08/15 17:4:
_	1	(polypropylene PP) near9 surface near9 (modif\$9 functionali\$8)	US-PGPUB;	
		near9 hydroxy\$2 near9 ((discharge near2 glow) plasma)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/08/15 17:4
	42	(( polyolefin polypropylene polyethylene) with (hydroxy\$2	USPAT;	2002/08/15 17.4
-	72	functionali\$7) with ((discharge near2 glow) plasma)) not ((	US-PGPUB;	
		polyolefin polypropylene polyethylene) near9 (hydroxy\$2	EPO; JPO;	
		functionali\$7) near9 ((discharge near2 glow) plasma))	DERWENT;	1
		Inuchoush ) hears ((meeting & nears from ) browns))	IBM TDB	
		DD) 1 (madiff() functionalif()) same	USPAT;	2002/08/15 17:4
-	383	(polypropylene PP) and surface near9 (modif\$9 functionali\$8) same	US-PGPUB;	
		((discharge near2 glow) plasma) same (hydroxy\$2 oxygen)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/08/15 17:4
_	127	(polypropylene PP) and surface near9 (modif\$9 functionali\$8) same	USPAT;	2002/00/13 17.5
-	121	((discharge near2 glow) plasma) same hydroxy\$2	US-PGPUB;	ļ
		(	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
	1	(polypropylene PP) same surface near9 (modif\$9 functionali\$8)	USPAT;	2002/08/15 17:
-	21	(polypropyletie FF) salite surface from (mounts) fame hydroxy\$?	US-PGPUB;	
	Ţ	same ((discharge near2 glow) plasma) same hydroxy\$2	EPO; JPO;	
			DERWENT;	
	1		IBM_TDB	
				2002/08/15 18:
_	143	polypropylene same surface near9 (modif\$9 functionali\$8) same	USPAT;	1
-	''	((discharge near2 glow) plasma)	US-PGPUB;	
	1	(\	ЕРО; ЈРО;	
	ļ		DERWENT:	
		•	IBM_TDB	

	56	polypropylene with surface near9 (modif\$9 functionali\$8) with	USPAT; US-PGPUB;	2002/08/15 17:56
		((discharge near2 glow) plasma)	ЕРО; ЈРО;	
			DERWENT,	
			IBM TDB	
		(polypropylene with surface near9 (modif\$9 functionali\$8) with	USPAT;	2002/08/15 18:17
	0	((discharge near2 glow) plasma)) with (air atmosphere oxygen)	US-PGPUB;	
	1	near5 (exposure subsequent\$5)	ЕРО; ЛРО;	
		near 3 (exposure subsequentas)	DERWENT,	
			IBM_TDB	
	1	(polypropylene with surface near9 (modif\$9 functionali\$8) with	USPAT;	2002/08/15 17:5
	1 1	((discharge near2 glow) plasma)) with (air atmosphere)	US-PGPUB;	
	1	((assessed 8 - 1 ) )	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
	18	(polypropylene same surface near9 (modif\$9 functionali\$8) same	USPAT;	2002/08/15 17:5
	"	((discharge near2 glow) plasma)) same (air atmosphere)	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
	45	(polypropylene same surface near9 (modif\$9 functionali\$8) same	USPAT;	2002/08/15 17:5
		((discharge near2 glow) plasma)) same (air atmosphere oxygen)	US-PGPUB;	
	1		EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	96	polypropylene same surface near9 (oxygen hydroxy\$2) near9	USPAT;	2002/08/15 18:0
		((discharge near2 glow) plasma)	US-PGPUB;	
		(" " " " " " " " " " " " " " " " " " "	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	2002/00/15 10:0
	106	polypropylene same surface near9 (oxygen hydroxy\$2) with	USPAT;	2002/08/15 18:0
		((discharge near2 glow) plasma)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/08/15 18:
	21	polypropylene same surface near9 hydroxy\$2 with ((discharge	USPAT; US-PGPUB;	2002/00/15 10.
		near2 glow) plasma)	EPO; JPO;	
			DERWENT;	
		1	IBM_TDB USPAT;	2002/08/15 18:
	3	surface near9 hydroxy\$2 with ((discharge near2 glow) plasma) with	US-PGPUB;	2002/00/15 10.
		(air atmosphere oxygen) near5 (exposure subsequent\$5)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	1	and the control of th	USPAT;	2002/08/15 18:
•	11	hydroxy\$2 with ((discharge near2 glow) plasma) with (air	US-PGPUB;	2002.30.12 10.
		atmosphere oxygen) near5 (exposure subsequent\$5)	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
		((discharge near2 glow) plasma) with (air atmosphere oxygen)	USPAT;	2002/08/15 19:
	10	((discharge near2 glow) plasma) with (all authosphere oxygen) near9 (exposure subsequent\$5) near9 hydroxy\$2	US-PGPUB;	
		neary (exposure subsequentias) nears flyddoxyd2	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	/-	silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r	USPAT;	2002/08/15 20:
-	67	Shalle hear a oxygen hear a plasma hear a (chemical hears support	US-PGPUB;	
		near3 deposition)	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	1

-	17	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r	USPAT;	2002/08/15 19:47
		near3 deposition)) with silicon near2 oxide	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
		0 (1	-	2002/08/15 19:48
-	0	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r	USPAT;	2002/06/13 17.40
		near3 deposition) ) with "SiO.sub.x"	US-PGPUB;	
			EPO; JPO; DERWENT;	
			1	
		0.41 1 2	IBM_TDB	2002/08/15 19:48
-	3	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r	USPAT;	2002/06/15 17.46
		near3 deposition) ) and "SiO.sub.x"	US-PGPUB;	
			EPO; JPO; DERWENT;	
			1	
		0 ( 1	IBM_TDB	2002/08/15 20:01
-	0	(silane near9 oxygen near9 plasma near9 (chemical near3 vapo\$1r	USPAT;	2002/08/15 20:01
		near3 deposition)) with polymerization near2 plasma	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
		0.7/1 1.1	IBM_TDB USPAT;	2002/08/15 20:16
-	3	silane near9 oxygen same plasma near9 ((chemical near3 vapo\$1r		2002/06/13 20:10
		near3 deposition) CVD) same polymerization	US-PGPUB;	
! !			EPO; JPO;	
1			DERWENT;	
1			IBM_TDB	2002/08/15 20:16
-	3	4557946.pn.	USPAT;	2002/08/13 20:10
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/09/16 11:20
l -	54	plasma near9 surface near9 silane near2 coupl\$7	USPAT;	2002/08/16 11:20
1			US-PGPUB;	
1			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/00/16 11:10
-	0	(plasma near9 surface near9 silane near2 coupl\$7) with hydroxy\$2	USPAT;	2002/08/16 11:19
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
		107 11 104	IBM_TDB	2002/08/16 14:43
-	10		USPAT;	2002/08/10 14.43
		chemical\$4 react\$7)	US-PGPUB;	
			EPO, JPO,	
			DERWENT,	
		A 107 34 1 1 A 107 34 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	IBM_TDB	2002/08/16 11:43
-	5	hydroxy\$4 near9 surface with silane near2 coupl\$7 with heat\$4	USPAT;	2002/00/10 11.43
		·	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	2002/09/16 11:56
-	3	hydroxy\$4 near9 surface with silane near2 coupl\$7 with (heat\$4	USPAT;	2002/08/16 11:56
		temperature) with react\$5	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/08/16 12:00
-	5	hydroxy\$4 near9 surface with silane near2 coupl\$7 with heat\$4	USPAT;	2002/08/16 12:00
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
1	1		IBM_TDB	1

	29	hydroxy\$4 with silane near2 coupl\$7 with heat\$4	001111,	2002/08/16 12:24
	23	nywonja i man osaasi	US-PGPUB;	
			EPO; JPO;	
	Į.		DERWENT;	
			IBM_TDB	2002/08/16 14:35
İ	49	"5229172"	USPAT;	2002/00/10 14.55
			US-PGPUB;	
	1		EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/08/16 14:35
	2	"6129956"	USPAT;	2002/08/10 14:55
	_		US-PGPUB;	
			ЕРО; ЛРО;	
	]		DERWENT;	
			IBM_TDB	2002/00/16 14:46
	ا ۱	alcohol near3 solution with silane near2 coupl\$5 with (heating	USPAT;	2002/08/16 14:46
	١	(elevated near2 temperature)) with hydroxy\$4	US-PGPUB;	
		(Cicvated near temperature )	ЕРО; ЛРО;	
			DERWENT;	
	[ [		IBM_TDB	
		alcohol near3 solution with silane near2 coupl\$5 with ((heating	USPAT;	2002/08/16 15:02
	0	heated) (elevated near2 temperature)) with hydroxy\$4	US-PGPUB;	ļ
		neated) (elevated hearz temperature)) was any a say	EPO; JPO;	ļ
			DERWENT;	
			IBM_TDB	
		alcohol with silane near2 coupl\$5 with ((heating heated) (elevated	USPAT;	2002/08/16 15:10
	0	near2 temperature)) with hydroxy\$4	US-PGPUB;	
		near2 temperature)) with hydroxys-	EPO; JPO;	
			DERWENT,	
			IBM_TDB	
		(alcohol with silane near2 coupl\$5 with hydroxy\$4) with surface	USPĀT;	2002/08/16 15:13
	9	(alcohol with silane near 2 couples 3 with hydroxys4) with salace	US-PGPUB;	
			ЕРО; ЛРО;	
	1		DERWENT;	
			IBM_TDB	
		400 111 1 04	USPAT;	2002/08/16 15:1
	51	alcohol with silane near2 coupl\$5 with hydroxy\$4	US-PGPUB;	2002/00/10
		·		
			EPO; JPO; DERWENT;	
			1	1
		1 .04	IBM_TDB   USPAT;	2002/08/16 16:1
	32	alcohol with silane near2 coupl\$5 with (chemical\$4 covalent\$4		2002/00/10 10:1
		react\$6) with surface	US-PGPUB;	
			EPO; JPO; DERWENT;	
			1	
			IBM_TDB	2002/08/16 16:3
_	117	alcohol with (aqueous water) with solution with ((coupling near2	USPAT;	2002/00/10 10.5
	1	agent) coupler silane) with (chemical\$4 covalent\$4 react\$6)	US-PGPUB;	
			EPO; JPO;	[
			DERWENT;	
			IBM_TDB	2002/00/16 16:
	73	kbm-602	USPAT;	2002/08/16 16:
-	'3		US-PGPUB;	
			EPO; JPO;	
	Ì		DERWENT;	
			IBM_TDB	
	1	dialkyldialkoxy\$1silane near6 (coupl\$7 (adhesion near2 promot\$5)	USPAT;	2002/08/16 17:
-	1	utathytutathonyutshaho nomo (voupto, (ustro-	US-PGPUB;	
		·	ЕРО, ЛРО;	
			DERWENT;	.
		1	IBM_TDB	1

Clarkly-disalkoxyS isilane dipropyldimethoxyS isilane) near6   USPAT;   U			•		
Comparison of the comparison	•	1			2002/08/16 16:42
DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO. DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO. DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO. DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO. DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO. DERWENT; IBM_TDB USPAT; US-PGPUB; PPO; PPO; PPO; PPO; PPO; PPO; PPO; PP			(couply/(adhesion near2 promots))		
IBM_TDB   IBM_					
2002/08/16 16:43  10 (dialkyldialkoxy\$1silane dipropyldimethoxy\$1silane) with heat\$9  11 dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  12 dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  13 dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  14 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  15 dialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  2002/08/16 17:41  2002/08/16 17:41  2002/08/16 17:41  2002/08/16 17:41  2002/08/16 17:51  2002/08/16 17:					
Classify disalkey shaded supply a state of the property of the parameters of the p					2002/09/16 16:42
Lego, Pro, DeRWENT; BM, TDB USPAT; US-RGPUB; EPO, Pro, DERWENT; BM, TDB US-RGPUB; EPO, Pro, DERWENT; BM, TDB US-RGPUB; EPO, Pro, DERWENT; BM, TDB US-RGPUB; EPO, Pro, DERWENT; BM, TDB US-RGPUB; EPO,	-	10	(dialkyldialkoxy\$1silane dipropyldimethoxy\$1silane) with heat\$9	-	2002/08/10 10:43
DERWENT: BIM TDB   DERWENT: BI					
dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  blackwild is contact the contact of the contact o					
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. 0 dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  124 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  1 dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  2 dialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  3 dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  4 deposition) with plasma with oxygen with plasma with oxygen with silicon near3 (oxide dioxide SiO)  5 dialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with p	-	0	dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with		2002/08/10 17.41
dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2\$)  124 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  125 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  126 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  127 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  128 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  129 blane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  120 clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  120 clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  120 clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  12002/08/16 17:41  128 pop(PUB, EPO, IPO, DERWENT, IBM_TDB USPAT, US-POP(UB, EPO, IPO, IPO, IBM_TDB USPAT, US-POP(UB, EPO, IPO, IPO, IPO, IBM_TDB USPAT, US-POP(UB, EPO, IPO, IPO, IPO, IPO, IPO, IPO, IPO, I			plasma with oxygen with silicon near3 (oxide dioxide SiO)	,	
dialkyldialkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  124 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  125 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  126 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  127 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  128 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  129 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  120 alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  120 bland dioxide SiO)  120 clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  12002/08/16 17:41  12002/08/16 17:51  128 PGPUB, EPO, IPO, DERWENT, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IBM IDB USPAT, US-PGPUB, EPO, IPO, IPO, IPO, IPO, IPO, IPO, IPO, I					
dialkyldialkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  124 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  125 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  126 silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  127 silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  128 silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  129 silane near4 (monomer organic alkyl) with (cvd (chemical near4 uspAT, uspAcpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspAT, uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspAT, uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, IPO, DERWENT, IBM_IDB uspAT, uspACpUB, EPO, IPO, DERWENT, IBM_IDB uspAT					
plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)  124 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  1			the state of the s		2002/09/16 17:41
EPO, IPO, DERWENT; BM_TDB USPAT; and silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  berwenty.  BM_TDB USPAT; US-PGPUB; EPO, IPO, DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO, DERWENT; ISM_TDB	-	0			2002/08/10 17.41
silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  berwent; BM, TDB USPAT; US-PGPUB; EPO, IPO, DERWENT; US-PGPUB; EPO, IPO, IPO, IPO, IPO, IPO, IPO, IPO, I			plasma with oxygen with silicon near3 (oxide dioxide SiO\$2)		
silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  blasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 oxide  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 oxide  clasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near9 (substrate surface) same silane near9 (substrate surface) same silane near9 (su					
silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  berwent;  BM_IDB  CO2/08/16 17:51  2002/08/16 17:51  2002/08/16 17:51  congression) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  congression) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  congression with cvd (chemical near4 deposition) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  congression with cvd (chemical near4 deposition) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  congression with silicon near3 (oxide dioxide SiO)  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition) with plasma  congression with silicon near4 deposition near4 deposition) with plasma  congression viting in plasma  congression plasma  congression plasma  congression plasma  congression plasma  congression plasma  congression plasma  congression p					
oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (evd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (evd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  silane near4 (monomer organic alkyl) with (evd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  [Po] DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, BM_TDB USPAT, US-PGPUB, EPO, JPO, DERWENT, US-PGPU					2002/09/16 17:51
alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  alkoxy\$1 silane with (cvd (chemical near4 with oxygen with silicon near3 (oxide dioxide SiO)  silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide deposition)) with plasma with oxygen with silicon near3 (oxide deposition)) with plasma with oxygen with silicon near3 (oxide deposition)) with plasma with oxygen with silicon near3 (oxide deposition)) with plasma with oxygen with silicon near3 (oxide deposition) DERWENT; libM_TDB usPAT; usPGPUB; ePO, IPO, DERWENT; libM_TDB usPAT; usPAT; usP	-	124			2002/08/16 17:51
alkoxy\$1 silane with (evd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 silane near4 (monomer organic alkyl) with (evd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  2002/08/16 17:48  USPAT, US-PGPUB, EPO, JPO, DERWENT, IBM, TDB	İ		oxygen with silicon near3 (oxide dioxide SiO)		
alkoxy\$1 silane with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  2002/08/16 17:48 USPAT; US-PGPUB; EPO, JPO, DERWENT; IBM, TDB					
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with oxygen with silicon near3 (oxide dioxide SiO)    Silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)   Silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)   Silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)   Silane near5 (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4   Compared to the plasma disharge) same (polyolefin polypropylene polyester plastic) near3 oxide   Silane near3 oxi	ł				
silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  27 ((plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  28 ((plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  29 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon plastic) same silane near3 coupl\$4  2003/04/04 17:16	-	0			2002/08/16 17:48
26 silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  2003/04/04 17:16			with oxygen with silicon near3 (oxide dioxide SiO)		
silane near4 (monomer organic alkyl) with (cvd (chemical near4 deposition)) with plasma with oxygen with silicon near3 (oxide dioxide SiO)  26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  2 ((plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  2 ((plasma disharge) same (polyolefin polypropylene polyester plastic) near3 oxide  3 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  4 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  5 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  5 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  5 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  5 ((plasma disharge) same (polyolefin polypropylene polyester plastic) uSPAT; uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uSPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; EPO; JPO; DERWENT; IBM_TDB uS-PGPUB; E					
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- 26 (plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  - 51 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4 same (silicon near3 oxide  - 0 ((plasma disharge) same (polyolefin polypropylene polyester plastic) USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO			dioxide SiO)		
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near9 (substrate surface) same silane near3 coupl\$4  US-PGPUB; EPO, JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; ISM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;					000000000000000000000000000000000000000
Compared to the compared of th	-	26	(plasma disharge) same (polyolefin polypropylene polyester plastic)		2003/04/04 17:16
Complete the complete polyment of the complete			near9 (substrate surface) same silane near3 coupl\$4		
Complete polyester plastic plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  51 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  51 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  52003/04/04 17:16  13 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  14 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4 same silicon near3 oxide  15 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4 same silicon near3 oxide  16 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4 same silicon near3 oxide  16 ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4 same silicon near3 oxide  17 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silomatic sam					
((plasma disharge) same (polyolefin polypropylene polyester plastic) near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  ((plasma disharge) same (polyolefin polypropylene polyester plastic) berwent; same silane near3 coupl\$4  ((plasma disharge) same (polyolefin polypropylene polyester plastic) berwent; same silane near3 coupl\$4 same silicon near3 oxide  ((plasma disharge) same (polyolefin polypropylene polyester plastic) berwent; same silane near3 coupl\$4 same silicon near3 oxide  3003/04/04 17:16  2003/04/04 17:16  2003/04/04 17:16  2003/04/04 17:16  2003/04/04 17:16  2003/04/04 17:16  2003/04/04 17:16					
near9 (substrate surface) same silane near3 coupl\$4) same silicon near3 oxide  US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO, IPO; DERWENT;				IBM_TDB	
near3 oxide    Periodic properties of the proper	-	0			2003/04/04 17:16
DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;					
- O ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - O ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon near3 oxide  - O (silane near3 coupl\$4) same (silicon near3 oxide)  - O ((plasma disharge) same (polyolefin polypropylene polyester plastic) USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JP			near3 oxide		
- S1 (plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4  - O ((plasma disharge) same (polyolefin polypropylene polyester plastic) DERWENT; IBM_TDB USPAT; Same silane near3 coupl\$4) same silicon near3 oxide  - 496 silane near3 coupl\$4 same (silicon near3 oxide)  - USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;					
same silane near3 coupl\$4  US-PGPUB; EPO; JPO; DERWENT; IBM_TDB US-PGPUB; Same silane near3 coupl\$4) same silicon near3 oxide  US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;					
Complete the complete same (polyolefin polypropylene polyester plastic) ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon near3 oxide  Complete the complete polyester plastic) (USPAT; USPGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; USPAT; USPGPUB; EPO; JPO; DERWENT; USPGPUB; EPO; JPO; DERWENT; USPGPUB; EPO; JPO; DERWENT;	-	51	(plasma disharge) same (polyolefin polypropylene polyester plastic)		2003/04/04 17:16
- Uspart; IBM_TDB Uspart; Uspa			same silane near3 coupl\$4		
- ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon near3 oxide  - 496 silane near3 coupl\$4 same (silicon near3 oxide)  IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; USPAT; US-PGPUB; EPO; JPO; DERWENT; EPO; JPO; DERWENT;	<u> </u>				
- ((plasma disharge) same (polyolefin polypropylene polyester plastic) same silane near3 coupl\$4) same silicon near3 oxide  USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT; DERWENT; DERWENT; DERWENT;					
same silane near3 coupl\$4) same silicon near3 oxide  US-PGPUB; EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; US-PGPUB; EPO; JPO; DERWENT;	İ				
EPO; JPO; DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; DERWENT; DERWENT;	-	0			2003/04/04 17:11
- 496 silane near3 coupl\$4 same (silicon near3 oxide)  DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	-		same silane near3 coupl\$4) same silicon near3 oxide		
- 496 silane near3 coupl\$4 same (silicon near3 oxide)  IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;					
silane near3 coupl\$4 same (silicon near3 oxide)  USPAT; US-PGPUB; EPO; JPO; DERWENT;					
US-PGPUB; EPO; JPO; DERWENT;					
EPO; JPO; DERWENT;	-	496	silane near3 coupl\$4 same (silicon near3 oxide)	,	2003/04/04 17:45
DERWENT;			-		
IBM_TDB					
· · · · · · · · · · · · · · · · · · ·				IBM_TDB_	

		avide)) and harrier	001111	2003/04/04 17:13	
	77 (		US-PGPUB;		
		`	ЕРО; ЛРО;		
			DERWENT;		
l			TRM TDB		
l l			USPAT;	2003/04/04 17:20	
Ì	1	(plasma discharge) same (polyolefin polypropylene polyester	US-PGPUB;		
	1	(plasma discharge) same (polyoletti polyptopytotic polyoletti polyoletti polyptopytotic polyoletti polyptopytotic polyoletti poly	EPO; JPO;		
ŀ		silicon near3 oxide	DERWENT;		
į	1	Sincon near 5 oxide			
ì			IBM_TDB	2003/04/04 17:18	
}			USPAT;	2003/04/01 21112	
l	2	(plasma discharge) same (polyoielli polypropylote personal plastic) and ((silane near3 coupl\$4 same (silicon near3 oxide)) and	US-PGPUB;		
}	1		EPO; JPO;		
1		barrier)	DERWENT;		
	ŀ		IBM_TDB	2002/04/04 17:20	
ļ	ļ	(plasma discharge) and ((silane near3 coupl\$4 same (silicon near3	USPAT;	2003/04/04 17:20	
_	46	(plasma discharge) and ((stiane hear) coupled state (	US-PGPUB;		
1		oxide)) and barrier)	ЕРО; ЈРО;		
ļ			DERWENT;		
			IBM_TDB		
		Salar and Calleng near Counts	USPAT;	2003/04/04 17:21	
	0	(plasma discharge) near9 pre\$1 treat\$9 and ((silane near3 coupl\$4	US-PGPUB;		
- į	Ū	same (silicon near3 oxide)) and barrier)	ЕРО; ЛРО;	İ	
1			DERWENT;	!	
İ			IBM TDB	İ	
1			USPAT;	2003/04/04 17:45	
	107	(plasma discharge) near9 (pre\$1treat\$9 treat\$9) and (silane near3		2005.0	
-	127	coupl\$4 same (silicon near3 oxide))	US-PGPUB;	1	
		coupl\$4 same (smooth nears 5.11-17)	ЕРО; ЛРО;		
			DERWENT;		
			IBM_TDB		
			USPAT;	2003/04/04 17:39	
_	21	"5131590"	US-PGPUB;	;	
-			ЕРО; ЛРО;		
			DERWENT;		
			IBM_TDB	1	
			USPAT;	2003/04/04 18:44	
	5	"5763028"	US-PGPUB;		
-			EPO; JPO;	` <b>\</b>	
			DERWENT		
			IBM_TDB	'	
	1			2003/04/07 15:32	
	9'	silane near3 coupl\$4 same (silicon near3 oxide) near3 (layer film)	USPAT;	1	
-			US-PGPUB	',	
			EPO; JPO;	.	
			DERWENT	,	
			IBM_TDB	2002/04/04 10:20	
		6 (plasma discharge) near9 (pre\$1treat\$9 treat\$9) and (silane near3	USPAT;	2003/04/04 18:2	
	1	6 (plasma discharge) neary (pres ideals y deals) discharge (plasma discharge) neary (pres ideals y deals)	US-PGPUE	3,	
		6 (plasma discharge) hear? (programmer (programmer) coupl\$4 same (silicon near3 oxide) near3 (layer film))	EPO; JPO;		
			DERWEN.	Γ;	
			IBM_TDB	i	
1			USPAT;	2003/04/04 18:4	
1	2438	plasma near3 discharge	US-PGPUI		
-	2438	plasma near services	EPO; JPO;		
			DERWEN		
	-	1			
	į		IBM_TDB	2003/04/04 20:4	
		3 (silane near3 coupl\$4 same (silicon near3 oxide) near3 (layer film	)) USPAT;	1	
-		3 (silane near3 coupl\$4 same (sincon near3 once)			
		and (plasma near3 discharge)	ЕРО; ЛРО	<u>;                                    </u>	
1			DERWEN	Π;	
	1	<b>,</b>	IBM_TDE	<b>₹</b>	

		<u> </u>		
	807	reactive near4 deposition near9 plasma	USPAT;	2003/04/04 20:47
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
i			IBM_TDB	
_	27	(reactive near4 deposition near9 plasma) same silane	USPAT;	2003/04/04 20:46
_	-		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	16	(reactive near4 deposition near9 plasma) with silane	USPĀT;	2003/04/04 20:48
-	10	(Teactive heart deposition nears plantial) was similar	US-PGPUB,	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
			1 -	2003/04/04 20:56
-	457	reactive near2 deposition near9 plasma	USPAT;	2003/04/04 20:30
			US-PGPUB;	
			EPO; JPO;	
	]		DERWENT;	
1			IBM_TDB	
l <u>.</u>	10	(reactive near2 deposition near9 plasma) with silane	USPAT;	2003/04/04 20:51
			US-PGPUB;	
			EPO; JPO;	
-		 	DERWENT;	
			IBM_TDB	
	15	(reactive near2 deposition near9 plasma) same silane	USPĀT;	2003/04/04 20:53
-	13	(Teactive hearz deposition hear) plasma) state state	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	_		USPAT;	2003/04/04 20:52
-	5	((reactive near2 deposition near9 plasma) same silane) not	US-PGPUB;	2005/01/01/20/22
1		((reactive near2 deposition near9 plasma) with silane)		
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/04/04 20 57
_	443	plasma same silane with oxygen same silicon near2 oxide	USPAT;	2003/04/04 20:57
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	14	(plasma same silane with oxygen same silicon near2 oxide) same	USPĀT;	2003/04/04 20:56
-	44	sputtering	US-PGPUB;	
		Spacesting	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	_	(plasma same silane with oxygen same silicon near2 oxide) same	USPAT;	2003/04/04 20:56
-	0		US-PGPUB;	
		reactive near2 sputtering	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	1	14 14		2003/04/04 20:56
-	4	reactive near2 deposition same (plasma same silane with oxygen	USPAT;	2003/04/04 20.30
1		same silicon near2 oxide)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	24	(plasma same silane with oxygen same silicon near2 oxide) same	USPAT;	2003/04/04 20:57
1	24	barrier	US-PGPUB,	
1		UMITE	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	J			<u></u>

-	96	silane near3 coupl\$4 with (Sio\$2 (silicon near3 oxide)) near3 (layer	USPAT;	2003/04/07 15:35
		film)	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
		#5C05026#	USPAT;	2003/04/07 20:14
-	4	"5695836"	US-PGPUB;	2000.0
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
_	2999	((silicon near3 (dioxide oxide mon\$2oxide)) SiOx) same sputtering	USPAT;	2003/04/07 19:01
		same plasma	US-PGPUB;	
		•	ЕРО; ЛРО;	
ļ			DERWENT;	
			IBM_TDB	2002/04/07 19:54
-	100	(((silicon near3 (dioxide oxide mon\$2oxide)) SiOx) same	USPAT;	2003/04/07 18:54
		sputtering same plasma) same silane same oxygen	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2003/04/07 18:54
-	40		USPAT; US-PGPUB;	2003/04/07 10.54
		sputtering same plasma) same silane same oxygen) and barrier	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	625	silicon near9 dioxide near9 (oxide mon\$20xide SiOx) with plasma	USPAT;	2003/04/07 19:03
-	635	silicon neary dioxide neary (oxide mont 20xide 510x) with plasma	US-PGPUB;	2005/0 11/07
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	1 1	silicon near9 dioxide near9 (oxide mon\$20xide SiOx) with plasma	USPAT;	2003/04/07 19:04
-	1	with silane with oxygen same barrier	US-PGPUB;	
		With Shalle With onlygen states of the state	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	3	silicon near9 dioxide near9 (oxide mon\$20xide SiOx) with plasma	USPAT;	2003/04/07 20:44
		with silane with oxygen and barrier near9 (oxygen gas)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2002/04/07 10:06
-	20	silicon near9 (dioxide oxide mon\$20xide SiOx) with plasma with	USPAT;	2003/04/07 19:06
		silane with oxygen and barrier near9 (oxygen gas)	US-PGPUB;	
			EPO; JPO;	
			DERWENT; IBM_TDB	
		11 01 11 with liver Clailers with save 194	USPAT;	2003/04/07 20:18
-	39	chlor\$1silane with alkoxy\$1silane with coupl\$6	US-PGPUB;	2003/04/07 20:10
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
	4	chlor\$1silane with alkoxy\$1silane with coupl\$6 with (hydroxy\$1	USPAT;	2003/04/07 20:16
-	4	oh) near2 group	US-PGPUB;	
		out and brook	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	39	(chlor\$1silane dichlor\$1silane) with alkoxy\$1silane with coupl\$6	USPAT;	2003/04/07 20:20
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	
			ЕРО; ЈРО;	1
			DERWENT;	
1			IBM_TDB	L

			· · · · · · · · · · · · · · · · · · ·	2002/04/07 20:10
<del></del> -	2	(chlor\$1 silane with alkoxy\$1 silane with coupl\$6) with alcohol	USPAT;	2003/04/07 20:19
		(011010.0111111111111111111111111111111	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	ا مدا	alkoxy\$1silane with coupl\$6 with alcohol	USPAT;	2003/04/07 20:31
	25	alkoxy51shalic with couples with account	US-PGPUB;	
		·	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
		100 11 1-1-1	USPAT;	2003/04/07 20:32
	59	alkoxy with silane near2 coupl\$6 with alcohol	US-PGPUB;	
			EPO; JPO;	
	1		DERWENT;	
			IBM_TDB	2003/04/07 20:36
	7	alkoxy with silane near2 coupl\$6 same solution near9 alcohol	USPAT;	2003/04/07 20:50
		•	US-PGPUB;	
	1		EPO; JPO;	
			DERWENT;	
	1		IBM_TDB	2002/04/07 20:20
	8	alkoxy with silane near2 coupl\$6 same solution near9 (ethanol	USPAT;	2003/04/07 20:38
	· ·	methanol alcohol)	US-PGPUB;	
		illediation alcohory	ЕРО; ЈРО;	
			DERWENT;	1
			IBM_TDB	
		2	USPAT;	2003/04/07 20:41
	2	silane near2 coupl\$6 same solution near9 (ethanol methanol	US-PGPUB;	
		alcohol) same heat\$6 same percent	EPO; JPO;	
			DERWENT;	
			IBM TDB	
	1		_	2003/04/07 21:10
	103	silane near2 coupl\$6 same solution near9 (ethanol methanol	USPAT;	2003/04/07 21.10
	1	alcohol) same heat\$6	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
	62	silane near2 coupl\$6 near9 solution near9 (ethanol methanol	USPAT;	2003/04/07 20:54
-	02	alcohol) same heat\$6	US-PGPUB;	
	1	alconol) same nearso	ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
		w 2 (1' wide wide) some ( silone near? count\$6 near9	USPAT;	2003/04/07 20:4
-	0	silicon near3 (dioxide oxide) same ( silane near2 coupl\$6 near9	US-PGPUB;	
		solution near9 (ethanol methanol alcohol) same heat\$6)	EPO; JPO;	
	1		DERWENT;	
			IBM TDB	
				2003/04/07 20:4
_	6	( silane near2 coupl\$6 near9 solution near9 (ethanol methanol	USPAT;	2003/04/07 20:1
		alcohol) same heat\$6) same (alkoxy methoxy ethoxy)	US-PGPUB;	
		,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
		( silane near2 coupl\$6 same solution near9 (ethanol methanol	USPAT;	2003/04/07 20:5
-	0	( silane near2 coupl\$6 same solution near9 (etitator nearant) alcohol) same heat\$6) same plasma near9 treat\$9	US-PGPUB;	
	1		EPO; JPO;	
			DERWENT;	
			IBM_TDB	
			. –	2003/04/07 20:
-	1	( silane near2 coupl\$6 same solution near9 (ethanol methanol	USPAT;	1
-		alcohol) same heat\$6) same plasma	US-PGPUB;	·
		,	ЕРО; ЛРО;	
			DERWENT	,
	1	1	IBM_TDB	1

-	silane near2 coupl\$6 same (ethanol methanol alcohol) same heat\$6 came (hydroxy\$1 oh)	USPAT; US-PGPUB; EPO; JPO; DERWENT:	2003/04/08 09:14
		IBM TDB	